# Compositional tailoring of the thermal expansion coefficient of tantalum (V) oxide

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The effect of  $Al_2O_3$  and  $Nb_2O_5$  additions on the microstructure and thermal expansion behavior of tantalum (V) oxide has been studied. Both singly doped and co-doped compositions were examined. Compositions with 3 wt%  $Al_2O_3$  (or greater), contained  $AlTaO_4$  as a second phase. Complete solubility was observed for  $Nb_2O_5$  contents in the range 1–5 wt%. It was found that doping with  $Al_2O_3$  results in a decrease of the coefficient of thermal expansion (CTE), such that increasing amounts of  $Al_2O_3$  (1–5 wt%) cause a successive decrease in the CTE value. In the case of  $Nb_2O_5$  additions, the result is an increase in the CTE of the tantalum (V) oxide. However, in the range 1–5 wt%  $Nb_2O_5$ , the CTE value is relatively insensitive to the amount of  $Nb_2O_5$  added. Due to the countervailing influences of these two additive oxides, it was demonstrated that co-doping with  $Al_2O_3$  and  $Nb_2O_5$  is an effective strategy for tailoring the CTE of tantalum (V) oxide. (V)

#### 1. Introduction

In terms of ceramic materials, silicon nitride (Si<sub>3</sub>N<sub>4</sub>) is one of the leading candidates for gas turbine engine applications. A critical issue in this application is the resistance of the material to environmental attack at elevated temperatures [1–4]. The combustion environment normally contains  $\sim 10\%$  water vapor, which due to the formation of volatile species, enhances the oxidation process in silicon based materials [2]. Accordingly, there has been strong interest in the development of an environmental barrier coating (EBC) for silicon nitride. A material which has been thought to have good potential as part of an EBC system for  $Si_3N_4$  is tantalum (V) oxide ( $Ta_2O_5$ ) [5–9]. A critical issue in the development of a successful EBC system is management of the thermal expansion mismatch between the coating and silicon nitride substrate. The objective of the present work is to explore compositional tailoring of the EBC as a means to control and optimize the thermal expansion mismatch.

Ta<sub>2</sub>O<sub>5</sub> cannot be used as coating material in the pure state, because it undergoes a series of phase transformations with increasing temperature. Because of the associated volume changes, these transformations are detrimental to the mechanical integrity of the sample [10– 13]. In this regard, the most critical phase transition is from the low-temperature orthorhombic ( $\beta$ ) phase, to the high-temperature tetragonal ( $\alpha$ ) phase, which takes place at ~1360°C. We have previously reported that Al<sub>2</sub>O<sub>3</sub>

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is a promising additive for  $Ta_2O_5$ , in that for a 3 wt% Al<sub>2</sub>O<sub>3</sub> addition, the phase transformation in Ta<sub>2</sub>O<sub>5</sub> is effectively suppressed, resulting in crack-free microstructures for samples fired at temperatures up to 1400°C [9]. Preliminary experiments also revealed that the addition of Al<sub>2</sub>O<sub>3</sub> results in a lowering of the coefficient of thermal expansion (CTE), whereas the addition of Nb<sub>2</sub>O<sub>5</sub> has the reverse effect. The aim of the present work was to explore more fully the effects of these two additive oxides on the thermal expansion behavior. Although there have been several papers describing modeling of multi-phase materials to determine the CTE of the composite [14–16], the authors are not aware of any experimental work on this topic as applied to Ta<sub>2</sub>O<sub>5</sub>. Moreover, by studying two oxides with opposing influences on the magnitude of the CTE, one aim of the study was to match the expansion behavior of Ta<sub>2</sub>O<sub>5</sub> to silicon nitride.

#### 2. Experimental

A series of  $Ta_2O_5$  specimens were prepared with varying amounts of  $Nb_2O_5$  and  $Al_2O_3$  additions. Samples were prepared containing 1, 3 and 5 wt%  $Nb_2O_5$ . A second series of samples was also prepared with the same  $Nb_2O_5$ content as above, (i.e., 1, 3 and 5 wt%), but with an additional 3 wt%  $Al_2O_3$ . This amount of alumina addition was selected based on previous work which showed that 3 wt% was sufficient to obtain a microcrack-free microstructure for sintering at temperatures up to  $1400^{\circ}$ C [9]. For reference purposes, a single phase sample of AlTaO<sub>4</sub> was also processed; this compound occurs as a second phase in Ta<sub>2</sub>O<sub>5</sub> – 3 wt% Al<sub>2</sub>O<sub>3</sub>, and forms when the amount of Al<sub>2</sub>O<sub>3</sub> added exceeds the solubility limit [9].

The starting materials were Ta<sub>2</sub>O<sub>5</sub> (Alfa Aesar, 99.993 %),  $\gamma$ -Al<sub>2</sub>O<sub>3</sub> (Alfa Aesar, 99.98 %, 0.01–0.02  $\mu$ m) and Nb<sub>2</sub>O<sub>5</sub> (99.9985 %, Alfa Aesar) powders. The powder preparation procedure was as follows. First, the various components were attrition milled for 3 h in isopropanol, using 1 mm TZP balls (Tosoh Corporation, Japan) as milling media. The milled mixtures were then dried with a Büchi rotary evaporator, ground with a mortar and pestle, and passed through a 80 mesh sieve to improve homogeneity. The sieved powders were subsequently isostatically compacted into bars  $(6 \times 6 \times 30 \text{ mm})$  in a rubber mold at 350 MPa, and fired at 1380°C for 5 h. All heat-treatments were carried out in a box furnace with a heating and cooling rate of 3°C/min. For comparison purposes, samples of undoped  $Ta_2O_5$  were prepared under the same conditions, except these were sintered at  $1320^{\circ}$ C to avoid the  $\beta$ -to- $\alpha$ phase transformation.

Phase identification for powder and fired samples was carried out using XRD (X-ray diffraction) measurements, which were made using a Rigaku horizontal wide angle goniometer (Model 2154D2). The X-ray source was a Rigaku Rotaflex RU-200B rotating anode generator with a copper anode, operated at 50 kV and 100 mA. The sintered microstructures were characterized by SEM (scanning electron microscopy, JEOL 6300F). Samples for SEM analysis were polished to a 1  $\mu$ m finish and thermally etched at 1290°C for 15 min.

Thermal expansion data was obtained on bar shaped specimens ( $4 \times 4 \times 25$  mm) using a Netzsch dilatometer (DIL 402C). The heating cycle consisted of heating up to 1250°C, and then immediately cooling down to room temperature. The heating and cooling rates were 3°C/min.



Figure 1 Expansion curves of Si<sub>3</sub>N<sub>4</sub>, Al<sub>2</sub>O<sub>3</sub>-doped and undoped Ta<sub>2</sub>O<sub>5</sub>.



*Figure 2* Microstructure of an as-fired surface of AlTaO<sub>4</sub> fired at  $1380^{\circ}$ C for 5 h (SEM).

Values of thermal expansion coefficients of the sintered samples were derived by linear fitting of the recorded data over a temperature span from room temperature up to  $1000^{\circ}$ C. For reference purposes, the thermal expansion behavior of a Si<sub>3</sub>N<sub>4</sub> sample (AS800, provided by the Honeywell Materials Technology Group) was also measured.

#### 3. Results and discussion

#### 3.1. $Ta_2O_5$ -Al<sub>2</sub>O<sub>3</sub> System

The expansion curves of Al<sub>2</sub>O<sub>3</sub>-doped and undoped Ta<sub>2</sub>O<sub>5</sub> are shown in Fig. 1. The corresponding data for the Si<sub>3</sub>N<sub>4</sub> sample and the AlTaO<sub>4</sub> are included for comparison. The thermal expansion coefficients of these materials were derived from Fig. 1, and the values are shown in Table I. The data shows that the undoped Ta<sub>2</sub>O<sub>5</sub> exhibits the highest CTE, and that the addition of increasing amounts of Al<sub>2</sub>O<sub>3</sub> successively lowers the value of the expansion coefficient. Given that the 3 wt% and 5 wt% Al<sub>2</sub>O<sub>3</sub> samples contain AlTaO<sub>4</sub> as a second phase, which itself has a CTE which is about a factor of 4 lower than that of Ta<sub>2</sub>O<sub>5</sub>, this result is expected. It can be seen from Fig. 1 that the expansion curve of the 1 wt% Al<sub>2</sub>O<sub>3</sub> sample has a reasonable match with that of Si<sub>3</sub>N<sub>4</sub>. Unfortunately, however, this

TABLE I  $\;$  Thermal expansion coefficients of  $Si_3N_4,\,Al_2O_3\mbox{-doped}$  and undoped  $Ta_2O_5$ 

	Thermal expansion coefficient (1/°C)
Si <sub>3</sub> N <sub>4</sub> (AS800)	$4.33 \times 10^{-6}$
Undoped Ta <sub>2</sub> O <sub>5</sub>	$6.72 \times 10^{-6}$
$Ta_2O_5$ doped with 1 wt% Al <sub>2</sub> O <sub>3</sub>	$3.27 \times 10^{-6}$
Ta <sub>2</sub> O <sub>5</sub> doped with 3 wt% Al <sub>2</sub> O <sub>3</sub>	$2.56 \times 10^{-6}$
Ta <sub>2</sub> O <sub>5</sub> doped with 5 wt% Al <sub>2</sub> O <sub>3</sub>	$1.95 \times 10^{-6}$
AlTaO <sub>4</sub>	$1.84 \times 10^{-6}$

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*Figure 3* XRD patterns of a  $\gamma$ -Al<sub>2</sub>O<sub>3</sub> and Ta<sub>2</sub>O<sub>5</sub> powder compact of AlTaO<sub>4</sub> composition before and after firing at 1380°C for 5 h. Note that the patterns of the powder mixture were consistent with orthorhombic Ta<sub>2</sub>O<sub>5</sub>, while those after firing were predominantly orthorhombic AlTaO<sub>4</sub>.



Figure 4 XRD patterns of 1 and 5 wt% Nb<sub>2</sub>O<sub>5</sub>-doped Ta<sub>2</sub>O<sub>5</sub> fired at  $1380^{\circ}$ C for 5 h.

composition would not be ideal for an EBC, because the additive level is insufficient to suppress the Ta<sub>2</sub>O<sub>5</sub>  $\beta$ -to- $\alpha$  phase transformation. A possible strategy, therefore, is to tailor the powder composition to offset the effect of the AlTaO<sub>4</sub> second phase on the thermal expansion of Ta<sub>2</sub>O<sub>5</sub>. It is perhaps worth mentioning that the value for the CTE of undoped tantalum (V) oxide obtained in the present study (6.72×10<sup>-6</sup>/°C), is higher than values reported previously in the literature [7, 19]. For example, Touloukian

TABLE II Thermal expansion coefficients of 1–5 wt%  $Nb_2O_5\mbox{-doped}\ Ta_2O_5$ 

Material	Thermal expansion coefficient (1/°C)
Ta <sub>2</sub> O <sub>5</sub> doped with 1 wt% Nb <sub>2</sub> O <sub>5</sub>	$7.78 \times 10^{-6}$
Ta <sub>2</sub> O <sub>5</sub> doped with 3 wt% Nb <sub>2</sub> O <sub>5</sub>	$7.98 \times 10^{-6}$
Ta <sub>2</sub> O <sub>5</sub> doped with 5 wt% Nb <sub>2</sub> O <sub>5</sub>	$8.30 \times 10^{-6}$







*Figure 5* Microstructures of (A) 1, (B) 3 and (C) 5 wt% Nb<sub>2</sub>O<sub>5</sub> doped Ta<sub>2</sub>O<sub>5</sub> fired at 1380°C for 5 h. Note that microcracking is present in all the samples, indicating partial  $\beta$ -to- $\alpha$  phase transformation took place during firing.

*et al.* [19] report a value of  $4.0 \times 10^{-6}$ /°C from 550 to 1200°C. The reason for this discrepancy is not known, but may be related to differences in the temperature range of study, and/or microstructural differences in the Ta<sub>2</sub>O<sub>5</sub> samples.

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Figure 6 Thermal expansion curves of Ta<sub>2</sub>O<sub>5</sub> doped with 1, 3 or 5 wt% Nb<sub>2</sub>O<sub>5</sub>. Corresponding data for Si<sub>3</sub>N<sub>4</sub>, AlTaO<sub>4</sub>, 3 wt% Al<sub>2</sub>O<sub>3</sub>-doped and undoped Ta<sub>2</sub>O<sub>5</sub> are included for comparison.



*Figure 7* XRD pattern obtained from  $Ta_2O_5$  sample containing 3wt%  $Al_2O_3$  and 5 wt%  $Nb_2O_5$ , fired at  $1380^{\circ}C$  for 5 h. The peaks marked with arrows correspond to AlTaO<sub>4</sub>, all other peaks correspond to the orthorhombic ( $\beta$ ) phase of  $Ta_2O_5$ .

The microstructure of the sintered AlTaO<sub>4</sub> sample is shown in Fig. 2. It can be seen that the sintering treatment resulted in a dense, fine-grained microstructure. Examination of this sample using XRD (see Fig. 3) revealed that it was predominantly orthorhombic AlTaO<sub>4</sub>, with a minor amount (<10%) of residual  $\beta$ -phase Ta<sub>2</sub>O<sub>5</sub>.

#### 3.2. Ta<sub>2</sub>O<sub>5</sub>-Nb<sub>2</sub>O<sub>5</sub> System 3.2.1. Phase identification and microstructure

Phase identification of the  $Ta_2O_5$  samples containing 1, 3 and 5 wt% Nb<sub>2</sub>O<sub>5</sub> was carried out using XRD, and the results are shown in Fig. 4. For ease of compar-

ison, only the XRD patterns from the two end compositions, i.e., 1 and 5 wt% Nb<sub>2</sub>O<sub>5</sub> are shown. It can be seen that the XRD patterns of the two samples appear almost identical; and correspond predominantly to the orthorhombic phase of Ta<sub>2</sub>O<sub>5</sub>. Two of the strongest peaks corresponding to the orthorhombic phase are the (0 1 0) at  $2\theta = 22.85^{\circ}$  (indicated by the solid circle), and the (11 0 2) at  $2\theta = 36.61^{\circ}$  (indicated by the arrow).

The microstructures of the fired samples are depicted in Fig. 5. The presence of microcracks was detected in all the samples, indicating that a partial  $\beta$ -to- $\alpha$  phase transformation had occurred during firing. The absence of second phase particles shows that Nb<sub>2</sub>O<sub>5</sub> forms a solid solution with Ta<sub>2</sub>O<sub>5</sub> at the additive levels studied. The above observations are consistent with previous phase equilibria studies in the Ta<sub>2</sub>O<sub>5</sub>-Nb<sub>2</sub>O<sub>5</sub> system [17, 18].

## 3.2.2. Thermal expansion studies on $Ta_2O_5$ -Nb<sub>2</sub>O<sub>5</sub> system

The thermal expansion curves of the Nb<sub>2</sub>O<sub>5</sub>-doped Ta<sub>2</sub>O<sub>5</sub> samples are shown in Fig. 6. The expansion curves of the AlTaO<sub>4</sub>, 3 wt% Al<sub>2</sub>O<sub>3</sub>-doped Ta<sub>2</sub>O<sub>5</sub> and AS800 Si<sub>3</sub>N<sub>4</sub> are also plotted for comparison. It can be seen that the addition of 1 wt% Nb<sub>2</sub>O<sub>5</sub> to Ta<sub>2</sub>O<sub>5</sub> results in an increase in the thermal expansion coefficient. With increasing Nb<sub>2</sub>O<sub>5</sub> content, there is little further change, so that the curves for the three Nb<sub>2</sub>O<sub>5</sub> - doped compositions are practically superposed. This result is also apparent from Table II, where it can be seen that the calculated values of CTE differ by less than 3%. The above results suggest a promising approach to modifying the thermal expansion behavior of Al<sub>2</sub>O<sub>3</sub>-doped Ta<sub>2</sub>O<sub>5</sub> to match that of AS800 Si<sub>3</sub>N<sub>4</sub>, i.e., co-doping with Nb<sub>2</sub>O<sub>5</sub>.

### 3.3. Ta<sub>2</sub>O<sub>5</sub> co-doped with Al<sub>2</sub>O<sub>3</sub> and Nb<sub>2</sub>O<sub>5</sub> 3.3.1. Phase identification and microstructure

Analysis of the co-doped Ta<sub>2</sub>O<sub>5</sub> samples using XRD revealed that for the Ta<sub>2</sub>O<sub>5</sub>-3 wt% Al<sub>2</sub>O<sub>3</sub>-*x* wt% Nb<sub>2</sub>O<sub>5</sub> compositions, where x = 1, 3 or 5, the patterns were very similar. Aside from two small peaks which correspond to the AlTaO<sub>4</sub> second phase, the peak positions and intensities were completely consistent with data which would be obtained for orthorhombic ( $\beta$ ) Ta<sub>2</sub>O<sub>5</sub>. Fig. 7 shows a XRD pattern which is representative of this series of compositions.

The microstructures of the fired samples are shown in Fig. 8. It can be seen that some degree of microcracking occurred in all samples, indicating that a partial  $\beta$ -to- $\alpha$  phase transformation took place during firing at 1380°C. This contrasts with the results for Al<sub>2</sub>O<sub>3</sub> additions only,



*Figure 8* Microstructures of  $Ta_2O_5$  doped with 3%  $Al_2O_3$  and various amount of  $Nb_2O_5$ : (A) 1%; (B) 3%; (C) 5%. Samples were fired at 1380°C for 5 h.

where it was observed that 3 wt%  $Al_2O_3$  was sufficient to stabilize the  $\beta$  structure at this temperature.

The reason for the difference in behavior is not fully understood, and requires further study. One possibility is that the effect of the  $Nb_2O_5$  is to negate the beneficial influence of  $Al_2O_3$  on the transition temperature. Alternately, we may speculate that the presence of dissolved  $Nb_2O_5$ 



Figure 9. Thermal expansion behavior of  $Ta_2O_5$  co-doped with 3 wt%  $Al_2O_3$  and 1, 3 or 5 wt%  $Nb_2O_5$ . Corresponding data for AITaO<sub>4</sub> and AS800  $Si_3N_4$  are included for comparison.

in the  $Ta_2O_5$  lattice reduces the solubility of  $Al_2O_3$ , and there is now insufficient alumina addition to completely suppress the transformation.

## 3.3.2. Thermal expansion studies on $Ta_2O_5/Al_2O_3/Nb_2O_5$ system

The thermal expansion curves of  $Ta_2O_5$  co-doped with 3 wt% Al<sub>2</sub>O<sub>3</sub> and 1–5 wt% Nb<sub>2</sub>O<sub>5</sub> are presented in Fig. 9, and the corresponding CTE values are given in Table III. The results show that the further addition of Nb<sub>2</sub>O<sub>5</sub> to the Al<sub>2</sub>O<sub>3</sub> containing compositions resulted in an overall increase in the CTE. Given that originally, the CTE of the Ta<sub>2</sub>O<sub>5</sub>- 3 wt% Al<sub>2</sub>O<sub>3</sub> composition was *below* that of the silicon nitride, this co-doping approach was successful in achieving a match with the thermal expansion coefficient of AS800 Si<sub>3</sub>N<sub>4</sub>. It can be seen from Fig. 9 that of the samples studied, the closest match is obtained with the Ta<sub>2</sub>O<sub>5</sub>-3 wt% Al<sub>2</sub>O<sub>3</sub> – 5 wt% Nb<sub>2</sub>O<sub>5</sub> composition.

TABLE III Thermal expansion coefficients of  $Ta_2O_5$ , AlTaO<sub>4</sub> and AS800 Si<sub>3</sub>N<sub>4</sub> ceramics in a temperature range up to  $1000^{\circ}C$ 

Material	Thermal expansion coefficient (1/°C)
$\label{eq:si3N4} \begin{array}{l} (AS800) \\ Ta_2O_5 \mbox{ doped with 3 wt% Al}_2O_3 \mbox{ and 1 wt% Nb}_2O_5 \\ Ta_2O_5 \mbox{ doped with 3 wt% Al}_2O_3 \mbox{ and 3 wt% Nb}_2O_5 \\ Ta_2O_5 \mbox{ doped with 3 wt% Al}_2O_3 \mbox{ and 5 wt% Nb}_2O_5 \\ \end{array}$	$\begin{array}{c} 4.33 \times 10^{-6} \\ 2.00 \times 10^{-6} \\ 2.54 \times 10^{-6} \\ 4.24 \times 10^{-6} \end{array}$

#### 4. Summary

The addition of Al<sub>2</sub>O<sub>3</sub> and Nb<sub>2</sub>O<sub>5</sub> can modify the thermal expansion coefficient of tantalum (V) oxide  $(Ta_2O_5)$ . Doping with Al<sub>2</sub>O<sub>3</sub> results in a decrease of the CTE, such that increasing amounts of Al<sub>2</sub>O<sub>3</sub> cause a successive decrease in the CTE value. This is attributed to the formation of a second phase, AlTaO<sub>4</sub>, which has a lower CTE than Ta<sub>2</sub>O<sub>5</sub>. In the case of Nb<sub>2</sub>O<sub>5</sub> additions, the result is an increase in the CTE of the tantalum (V) oxide. However, in the range 1-5 wt%, the Nb<sub>2</sub>O<sub>5</sub> forms a solid solution, and the CTE value is relatively insensitive to the amount of Nb<sub>2</sub>O<sub>5</sub> added. Due to the countervailing influences of these two additive oxides, it was demonstrated that codoping with Al<sub>2</sub>O<sub>3</sub> and Nb<sub>2</sub>O<sub>5</sub> is an effective strategy for tailoring the CTE of tantalum (V) oxide. From the standpoint of potential applications of Ta<sub>2</sub>O<sub>5</sub> as part of an EBC system for silicon nitride, closest matching was obtained with the composition  $Ta_2O_5 - 3 \text{ wt\%} Al_2O_3 - 5 \text{ wt\%}$  $Nb_2O_5$ .

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